L Number	Hits	Search Text	DB	Time stamp
_ number	4	"200012465"	EPO; JPO;	2003/11/04 10:06
	*	200012103	DERWENT	
-	11	"12465"	EPO; JPO; DERWENT	2003/11/03 13:00
-	0	"P200012465"	EPO; JPO; DERWENT	2003/11/03 13:01
-	2	"09237927"	EPO; JPO; DERWENT	2003/11/03 13:01
_	2	5866471.pn.	EPO; JPO; DERWENT	2003/11/04 08:28
-	1	5866471.pn.	USPAT;	2003/11/04 08:28
_	30	(Furusawa.in. or Miyashita.in. or	US-PGPUB USPAT;	2004/04/22 13:52
		Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or	US-PGPUB; EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((silicon or Si) near2	IBM TDB	
ļ		(coat\$3 or film or layer or deposit\$3))	_	
		and ((ring adj silane) or (cyclic adj		
		silane) or cyclosilane or cyclopentasilane		
		or Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
	1.0	cyclopentasilane))	EDO. TDO.	2003/11/04 10:29
-	19	"59015"	EPO; JPO; DERWENT;	2003/11/04 10:29
			IBM TDB	
_	2	"200059015"	EPO; JPO;	2003/11/04 10:29
			DERWENT;	
		W000050044W	IBM_TDB EPO; JPO;	2003/11/04 11:08
-	2	"200059044"	DERWENT;	2003/11/04 11:00
			IBM TDB	
_	1420	(427/552,553,555,558).CCLS.	USPAT;	2004/04/22 15:34
			US-PGPUB	
_	1056	(427/226).CCLS.	USPAT; US-PGPUB	2003/11/04 11:09
-	2229	((427/248.1,255.18,255.23) or	USPAT;	2004/04/22 15:35
		(438/503,507)).CCLS.	US-PGPUB	0004/04/00 45 05
-	2859	(427/258,259,261,264,265,270,271).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	417	(423/348,349).CCLS.	USPAT;	2004/04/22 15:35
_	519	(117/88,95).CCLS.	US-PGPUB USPAT;	2004/04/22 15:35
	0100	(//27/552 553 555 550) CCIC \	US-PGPUB USPAT;	2004/04/23 09:14
_	8126	((427/552,553,555,558).CCLS.) ((427/226).CCLS.)	US-PGPUB	2004/04/23 09:14
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.)		
-	14	(((427/552,553,555,558).CCLS.)	USPAT;	2004/04/22 15:37
		((427/226).CCLS.)	US-PGPUB	
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
		and ((silicon or Si) near2 (coat\$3 or film		
	į	or layer or deposit\$3)) and ((ring adj		
		silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
+		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))	_	
L		Olorobourgoliumo//	l	

Page 1

_	3	(((427/552,553,555,558).CCLS.) or ((427/258,259,261,264,265,270,271).CCLS.)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/04/22 15:39
_	32		USPAT; US-PGPUB	2004/04/22 15:40
_	15	(((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)) and (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or fluoroalkyl or fluorine or SAM or (self adj assembl\$3) or fluoro\$12) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))	USPAT; US-PGPUB	2004/04/22 15:40
-	694	(((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or fluoroalkyl or fluorine or SAM or (self adj assembl\$3) or fluoro\$12) with (mask\$3 or inactiv\$5 or (in adj activ\$5))	USPAT; US-PGPUB	2003/11/04 11:32
-	59		USPAT; US-PGPUB	2003/11/04 12:54
	53	<pre>((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5))) not (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)) and (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform)) and ((monolayer or (mono adj layer) or fluoroalkyl or fluorine or SAM or (self adj assembl\$3) or fluoro\$12) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5))))</pre>	USPAT; US-PGPUB	2003/11/04 11:33
L		accounty of (ac au accivyo))))	<u></u>	l

layer or deposit\$3 or \$4CVD or vaporis\$5) with (select\$? or pattern\$3 or nonuniform or (non adj uniform)) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5)) or ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporis\$5)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) def (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporis\$5)) and (monolayer or (mono adj layer) or sAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) def (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporis\$5)) and ((monolayer or (mono adj layer) or sAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and ((monolayer or (mono adj layer) or sAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (madj activ\$5) or pattern\$3)) and (monolayer or (mono adj layer) or sAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (madj activ\$5) or pattern\$3]) and (((ad7/552,553,555,558).CLLS.) ((427/228,1255,235,555,558).CLLS.) ((427/228,1255,235,555,558).CLLS.) ((427/228,1255,236,262,264,265,270,271).CCLS.) ((427/228,1255,270,271).CCLS.) ((427	layer or deposit\$3 or \$4(VV) or vapor(125))	layer or deposit\$3 or \$4CVD or vaporiz\$5) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform)) and ((monolayer or (mono adj uniform))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (adj activ\$5))					
with (selects? or pattern\$3 or nonuniform or (non adj uniform)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5)) (((silicon or Si) near2 (coat\$3 or film or layer) or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) - 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) - 7 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3)) - 8 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or sAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or or battern\$3)) and ((((427/525, 555, 555, 558).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((127/256, 555, 555, 558).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((127/256, 559, 555, 598).CCLS.) ((427/256).CCLS.) ((127/256).CCLS.) ((127/256).CC	with (selects? or patterns3 or nonuniform or (non adj uniform)) and ((monolayer or (mono adj layer) or SAM or (self adj assembls3)) with (mask3 or inactiv55 or (de adj activ55)) or deactiv55 or (de adj activ55)) or deactiv55 or (de adj activ55)) and ((monolayer or (mono adj layer) or SAM or (self adj assembls3)) with (mask3 or inactiv55 or (in adj activ55)) with (mask3 or inactiv55 or (in adj activ55) or deactiv55 or (de adj activ55) - 466 (((sellicon or Si) near2 (coat33 or film or layer or deposit3 or SACVD or vaporiz55))) and ((monolayer or (mono adj layer) or SAM or (self adj assembls3)) with (mask3 or inactiv55 or (de adj activ55) or patterns3)) - 27 (((sellicon or Si) near2 (coat33 or film or layer or deposit3 or SACVD or vaporiz55))) and (monolayer or (mono adj layer) or SAM or (self adj assembls3)) with (mask3 or inactiv55 or (de adj activ55) or patterns3)) with (mask3 or inactiv55 or (de adj activ55) or patterns3)) and (((427/525,533,555,558).CCLS.)) ((427/226).CCLS.) ((427/2	with (select37 or pattern\$3 or nonuniform or (non adj uniform)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask3 or inactiv\$5 or (de adj activ\$5))	-	2	(((silicon or Si) near2 (coat\$3 or film or	EPO; JPO;	2003/11/04 11:39
or (non adj uniform)) and ((monolayer or (mono adj layer) or SAM or (self adj assembly3)) with (mask83 or inactiv85 or (de adj activ85))) 7 (((silicon or Si) near2 (coat83 or film or layer or deposit83 or \$4CVD or vaporiz85))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) 466 ((silicon or Si) near2 (coat83 or film or layer or deposit83 or \$4CVD or vaporiz85)) and (donolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83)) with (mask83 or inactiv85 or (in adj activ85) or pattern83) with (mask83 or inactiv85 or (in adj activ85) or (in adj acti	or (mon adj uniform)) and (monolayer or (mono adj layer) or SAM or (self adj assembl(33)) with (mask%3 or inactiv%5 or deactiv%5 or deactiv%5) or deactiv%5 or deactiv%5 or deactiv%5 or deactiv%5 or deactiv%5 or deactiv%5 or deactiv%5) or deactiv%5 or deactiv%5 or deactiv%5) or deactiv%5 or deactiv%5 or deactiv%5) or deactiv%5 or deactiv%5) or deactiv%5 o	or (non adj uniform))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (adj activ\$5))) 7 (((silicon or Si) near2 (coat\$3 or film or layer) or deposit\$3 or \$4CVD or vapor12\$\$1)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5)) or deactiv\$5) or (deadj activ\$5)) or deactiv\$5 or (de adj activ\$5) or deactiv\$5 or (de adj activ\$5) or deactiv\$5) or deactiv\$5 or (in adj activ\$5) or pattern\$3]) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (in adj activ\$5) or pattern\$3]) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) and (((a27/258, 259, 261, 264, 265, 270, 271).CCLS.) (((427/258, 259, 261, 264, 265, 270, 271).CCLS.) (((427/258, 259, 261, 264, 265, 270, 271).CCLS.) (((127/248, 1, 255, 181)) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (deadj activ\$5) or deactiv\$5] or			layer or deposit\$3 or \$4CVD or vaporiz\$5))	1	
(mono adj layer) or SAM or (self adj assembl\$3) with (mask\$3 or inactiv\$5 or (de adj activ\$5)) or deactiv\$5 or (de adj activ\$5)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or sAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and (((2477/526,555,555,558).CCLS.) ((4277/226,525,555,558).CCLS.) ((4277/226,CCLS.) ((4277/226,CCLS.) ((4277/226,CCLS.) ((1277/88,95).CCLS.)) ((1277/88,97).CCLS.) ((4277/236,CS),567,578).CCLS.) ((4277/236,CS),567,578).CCLS.) ((4277/236,CS),567,578).CCLS.) ((4277/236,CS),567,578).CCLS.) ((1277/88,97).CCLS.) ((1277/88,97).CCL	(mono add] layer) or SAM or (self add) assembl(\$3) with (mask3 or inactiv\$5 or (in add) activ\$5) or deactiv\$5 or (de add) activ\$5))) (((silicon or Si) near2 (coat\$3 or film or layer) or sAM or (self add) assembl(\$3)) with (mask3 or inactiv\$5 or (in add) activ\$5)) or deactiv\$5 or (de add) activ\$5) or pattern\$3]) - 466 ((islicon or Si) near2 (coat\$3 or film or layer) or SAM or (self add) assembl(\$3)) with (mask3 or inactiv\$5 or (in add) activ\$5) or deactiv\$5) or (de add) activ\$5) or pattern\$3]) - 27 (((islicon or Si) near2 (coat\$3 or film or layer) or SAM or (self add) assembl(\$3)) with (mask3 or inactiv\$5 or (in add) activ\$5) or deactiv\$5 or (de add) activ\$5) or pattern\$3]) - 27 ((((slilicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono add) layer) or SAM or (self add) assembl\$3)) with (mask3 or inactiv\$5 or (in add) activ\$5) or deactiv\$5 or (de add) activ\$5) or locativ\$5 or (la add) ac	(mono adj layer) or SAM or (self adj assembl33) with (mask3 or inactiv55 or (de adj activ55)) or deactiv55) or (de adj activ55)); and (imonolayer or (mono adj layer) or SAM or (self adj assembl33)) with (mask3 or inactiv55 or (in adj activ55) or pattern53); with (mask3 or inactiv55 or (in adj assembl33)) with (mask3 or inactiv55 or (in adj activ55)) or pattern53); with (mask3 or inactiv55 or (in adj activ55) or pattern53); with (mask3 or inactiv55 or (in adj activ55) or pattern53); with (mask3 or inactiv55 or (in adj activ55) or pattern53); with (mask3 or inactiv55 or (in adj activ55) or pattern53); with (mask3 or inactiv55 or (in adj activ55) or deactiv55 or (de adj activ55); ((427/525,253,555,558), ccls.); ((427/226,1254,253,555,558), ccls.); ((427/226,1254,253,555,558), ccls.); ((427/226,1254,253,555,558), ccls.); ((427/226,1254,253,555,558), ccls.); ((427/226,1254,255,256,1254,256,276,271), ccls.); ((427/226,1254,256,1254,256,276,271), ccls.); ((427/226,1254,256,1254,256,276,271), ccls.); ((427/226,1254,256,1254,256,276,271), ccls.); ((427/226,1254,256,1254,256,276,271), ccls.); ((427/226,1254,256,1254,256,276,271), ccls.); ((427/226,1254,256,1254,256,276,271), ccls.); ((427/226,1254,256,276,271), ccls.); ((427/2	İ			IBM_TDB	
assembls3) with (mask83 or inactiv\$5 or (de adj activ\$5)) or (deactiv\$5) or (de adj activ\$5)) or (deactiv\$5) or (in adj activ\$5) or deactiv\$5 or (in adj activ\$5) or deactiv\$5 or (in adj activ\$5) or deactiv\$5 or (deadj activ\$5) or pattern\$3)) 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3)) vith (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) cor pattern\$3)) 27 ((((silicon or Si) near2 (coat\$3 or film or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) with (mask\$3 or inactiv\$5 or (in ond adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))) and (((27)752,53,555,558).CCLS.) ((427)728,55,253,555,558).CCLS.) ((427)728,55,256,261,264,265,270,271).CCLS.) ((427)728,55,261,264,265,270,271).CCLS.) ((427)728,55,261,264,265,270,271).CCLS.) ((427)728,55,261,264,265,270,271).CCLS.) ((427)728,55,261,264,265,270,271).CCLS.) ((427)728,55,261,264,265,270,271).CCLS.) ((427)728,55,261,264,265,270,271).CCLS.) ((427)728,55,261,264,265,270,271).CCLS.) ((427)728,550,261,264,265,270,271).CCLS.) ((427)728,5	assembls3) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)) 7 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl83)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3)) 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl83)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3)) and (monolayer or (mono adj layer or deposit\$3 or \$4CVD or vaporiz\$5))) and (monolayer or (mono adj layer or deposit\$3 or \$4CVD or vaporiz\$5)) or pattern\$3]) and (monolayer or (mono adj layer or deposit\$3 or \$4CVD or vaporiz\$5)) or deactiv\$5 or (de adj activ\$5) or deactiv\$5 or (activ\$5) or (activ\$5) or deactiv\$5 or (mono adj layer) or SAM or (self adj activ\$5) or (activ\$5)	assembl\$3)					
(in adj activ\$5) or deactiv\$5 or (de adj activ\$5)) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) 7 (((silicon or Si) near2 (coat\$3 or film or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) 7 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))) and (((427/226, 553, 555, 558).CCLS.)) ((427/226, CCLS.) ((427/226, CCLS.) ((127/28, 439).CCLS.) ((117/88, 95).CCLS.)) ((427/226, CCLS.) ((17/88, 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or (self adj assembl\$5) or or deactiv\$5) or (de adj activ\$5) or (de a	(in adj activ\$5) or deactiv\$5 or (de adj activ\$5)	(in adj activ\$5) or deactiv\$5 or (de adj activ\$5)) 7 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$\$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or or deactiv\$5) or deactiv\$5 or (de adj activ\$5) or or deposit\$3 or \$\$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5) or deactiv\$5 or (de adj activ\$5) or deactiv\$5) or deactiv\$5 or (de adj activ\$5) or deactiv\$5 or deactiv\$5 or (de adj activ\$5) or patterns3)) and (monolayer or (mono adj layer) or \$\$3M or (self adj assembl\$3)) under (((427/528,259,555,558).CCLS.) ((427/268,128,259,261,264,265,270,271).CCLS.) ((427/268,128,259,261,264,265,270,271).CCLS.) ((427/268,128,259,261,264,265,270,271).CCLS.) ((427/268,128,259,261,264,265,270,271).CCLS.) ((107/266,128,137)) same (monolayer or (mono adj layer) or \$\$3M or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or deactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) o		İ			
activ\$5))) 7 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vapor1z\$5)) and ((monolayer or (mono adj layer)) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3]) 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vapor1z\$5))) and ((monolayer or (mono adj layer)) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) 7 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vapor1z\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) 8 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vapor1z\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3]) activ\$5 or jor deactiv\$5 or (de adj activ\$5) or pattern\$3]) (((427/258, 253, 255, 258), CCLS.) ((427/226, CCLS.) ((427/226, CCLS.) ((427/226, CCLS.) ((427/226, CCLS.) ((427/238, 249), CCLS.) ((427/258, 259, 261, 264, 265, 270, 271), CCLS.) ((427/258, 259, 261, 264, 265, 270, 271), CCLS.) ((427/258, 259, 261, 264, 265, 270, 271), CCLS.) ((427/368, 249), CCLS.) ((147 (refas layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or or deactiv\$5 or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or or deactiv\$5 or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or or deactiv\$5 or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj	activ\$\$)))	activs5))) 7 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adjlayer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adjactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or pattern\$3)) 466 (((silicon or Si) near2 (coat\$3 or film or layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adjactiv\$5) or deactiv\$5) or deactiv\$5 or (de adjactiv\$5) or pattern\$3)) 47 (((silicon or Si) near2 (coat\$3 or film or layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adjactiv\$5) or pattern\$3)) with (mask\$3 or inactiv\$5 or (mono adjlayer) or SAM or (self adjactiv\$5) or pattern\$3)) with (mask\$3 or inactiv\$5 or (in adjactiv\$5) or deactiv\$5 or (deadjactiv\$5) or deactiv\$5 or (deadjactiv\$5) or pattern\$3)) and (((1427/525,253,555,555,558).CCLS.) ((427/248,1,255,18,255,23) or (438/503,507)).CCLS.) ((427/248,1,255,18,255,23) or (438/503,507)).CCLS.) ((427/248,1,255,18,255,23) or (438/503,507)) or pattern or mask\$3 or (Fab is) or pattern or mask					
	-	7 (((silicon or Si) near2 (coat33 or film or layer or deposit30 or \$40CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or \$AM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (do adj activ\$5) or pattern\$3)) 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$40CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or \$AM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (do adj activ\$5) or pattern\$3)) 7 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$40CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or \$AM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (do adj activ\$5) or deactiv\$5 or (do adj activ\$5) or deactiv\$5 or (do adj activ\$5) or deactiv\$5 or (do adj activ\$5) or (427/252, 553, 555, 558). CCLS.) ((427/252, 553, 555, 558). CCLS.) ((427/268, 259, 251, 264, 265, 270, 271). CCLS.) ((427/268, 259, 251, 261, 264, 265, 270, 271). CCLS.) ((427/268, 259, 251, 261, 264, 265, 270, 271). CCLS.)					
layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3)) 466 ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3)) 47 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assemb]\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and ((monolayer or (mono adj layer) or SAM or (self adj assemb]\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and ((427,752,553,555,558).CCLS.) ((427,726, CCLS.) ((427,726, CCLS.) ((427,726, CCLS.) ((427,726, CCLS.)) ((427,726,	layer or deposit\$3 or \$4CVD or vaporiz\$51); and ((monolayer or (mono adj layer) or SAN or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$31) 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$51)) and ((monolayer or (mono adj layer) or SAN or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$31) 27 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$51)) and (monolayer or (mono adj layer) or SAN or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$31) 27 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$51)) and ((monolayer or (mono adj layer) or SAN or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$31)) and (((4277/248, 1,255, 18,255, 23) or (4387/503,507), CCLS.) ((4277/248, 1,255, 18,255, 23) or (4387/503,507), CCLS.) ((4277/248, 1,255, 18,255, 23) or (4387/503,507), CCLS.) ((4277/248, 1,255, 18,255, 23) or (4387/503,507), CCLS.) ((127/348, 349), CCLS.) ((117/88, 95), CCLS.)) ((127/348, 349), CCLS.) ((117/88, 95), CCLS.)) ((127/348, 349), CCLS.) ((117/88, 95), CCLS.)) ((127/348, 139), CCLS.) ((127/248, 1255, 18,255, 23) or (187, 187), CCLS.) ((127/248, 1255, 18,255, 18	layer or deposit\$3 or \$4CVD or vaporix\$5)] and ((monolayer or (mono adj layer) or \$3M or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3)]					
vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) with (monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and ((monolayer or (mono adj layer) or SAM or (self adj activ\$5) or pattern\$3)) and (((4277256,2553,555,558).CCLS.) ((4277226,2553,555,558).CCLS.) ((4277226,259,261,264,265,270,271).CCLS.) ((4277256,259,261,264,265,270,271).CCLS.) ((4277256,259,261,264,265,270,271).CCLS.) ((4277256,259,261,264,265,270,271).CCLS.) ((4277256,259,261,264,265,270,271).CCLS.) ((4277256,050,259),261,264,265,270,271).CCLS.) ((4277256,050,259),261,264,265,270,271).CCLS.) ((4277256,050,259),261,264,265,270,271).CCLS.) ((4277256,050,259),261,264,265,270,271).CCLS.) ((4277256,050,259),261,264,265,270,271).CCLS.) ((4277256,050,259),261,264,265,270,271).CCLS.) ((4277256,050,259),261,264,265,270,271).CCLS.) ((4277256,050,250,250,250),261,264,265,270,271).CCLS.) ((4277256,050,250,250,250,250,250,250,250,250,250	vaporiz55))) and ((monolayer or (mono add) layer) or SAN or (self add) ascembl33) with (mask83 or inactiv\$5 or (in add) activ\$5) or pattern\$3])	vaporix\$5) and ((monolayer or (mono adj layer) or \$8M or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))	-	′	(((Silicon or Si) near2 (coat33 or film or		2003/11/04 11:42
layer) or SAM or (self adj assembla3)	layer) or SAM or (self adj assembl\$3) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$31)	layer) or SAM or (self adj assembl\$3)					1
### with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3]) ### d66 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or (mono adj layer) or \$SAM or (self adj assembl\$3)) ### with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3]) ### or layer or deposit\$3 or \$4CVD or (mono adj layer) or \$SAM or (self adj activ\$5) or pattern\$3]) ### or layer or deposit\$3 or \$4CVD or vaporiz\$5]) and ((monolayer or (mono adj layer) or \$SAM or (self adj assembl\$3)) ### with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3]) in and (monolayer or (mono adj layer) or \$SAM or (self adj assembl\$3)) ### (427/25\$) (553,555,558) (CLS.) ### (427/25\$) (553,555	with (mask3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3]) 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3]) 70 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3])) with (mask3 or inactiv\$5 or (in adj activ\$5)) or deactiv\$5 or (de adj activ\$5) or pattern\$3])) with (mask3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3])) with (mask3 or inactiv\$5 or (in adj activ\$5) or (ata27/256, 253, 555, 558), CCLS.) ((427/256, CCLS.) ((427	with (mask3 or inactiv\$5 or (in adj activ\$5) or pattern3) - 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) - 27 ((((silicon or Si) near2 (coat\$3 or film or or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask3 or inactiv\$5 or (in adj activ\$5) or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))) and (((2427/525, 525, 555, 558).CCLS.) ((4277/226).CCLS.) ((4277/226).CCLS.) ((4277/226).CCLS.) ((4277/226).CCLS.) ((1277/226).CCLS.) ((1277/226).				TBW_LDB	[
activ\$\$) or deactiv\$\$ or (de adj activ\$\$) or pattern\$3)) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$\$))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (de adj activ\$5) or layer or deposit\$3 or \$4CVD or vaporiz\$\$))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3)) and (((427/526, CCLS.)) ((427/2261, CCLS.)) ((427/2261, CCLS.)) ((427/2263, 259, 261, 264, 265, 270, 271). CCLS.) ((427/258, 259, 261, 264, 265, 270, 271). CCLS.) ((427/258, 259, 261, 264, 265, 270, 271). CCLS.) ((427/268, 138)) or monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) - 60 ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj activ\$5) or deactiv\$5) - 60 ((tridecafluoro near5 triethoxysilane) or (mono adj layer) or SAM or (self adj activ\$5) or deactiv\$5) - 60 ((tridecafluoro near5 triethoxysilane) or (mono adj layer) or SAM or (self adj activ\$5) or deactiv\$5) - 7 60 (mono adj layer) or SAM or (self adj activ\$5) or deactiv\$5) - 8 6 6 6 6 7 6 7 7 7 8 13") and (monolayer or (mono adj layer) o	activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$31) - 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) - 27 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))) and (((427/525, 253, 555, 558).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/226, 259, 261, 264, 265, 270, 271).CCLS.) ((427/226, 259, 261, 264, 265, 270, 271).CCLS.) ((427/236, 259, 261, 264, 265, 270, 271).CCLS.) ((427/236) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5 - 1 ((tridecafluoro near3 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (activ\$5) or (ac	activ§5) or deactiv§5 or (de adj activ§5) or pattern§3) 466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or \$8M or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5) or deactiv\$5 or (de adj activ\$5) or pattern§3) 727 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or \$8M or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) and (monolayer or (mono adj layer) or \$8M or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) and ((427/252, 553, 555, 558).CCLS.) ((427/252, 553, 555, 558).CCLS.) ((427/268, 1.255.18, 255.23) or (438/503, 507). CCLS.) ((427/268, 1.255.18, 255.23) or (438/503, 507). CCLS.) ((427/268, 1.255.18, 255.23) or (438/503, 507). CCLS.) ((117/88, 95).CCLS.) ((427/268, 1.255.18, 255.23) or (438/503, 507). CCLS.) ((117/88, 95).CCLS.) ((117/88, 95					
def (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$31)	466	or pattern\$3]) (((silicon or \$i) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5])) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) 27 ((((silicon or \$i) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5])) and ((monolayer or (mono adj layer)) or SAM or (self adj assembl\$3]) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3])) and ((monolayer or (mono adj layer)) or SAM or (self adj assembl\$3]) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3])) and (((4277258, 259, 261, 264, 265, 270, 271). CCLS.) ((4277248, 1, 255, 18, 255, 23) or (4387503, 507)). CCLS.) ((4277248, 1, 255, 18, 255, 23) or (mono adj layer) or SAM or (self adj assembl\$5] or pattern or mask\$3 or inactiv\$5 or (activ\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5 or (activ\$5) or of captiv\$5] ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (activ\$5) or pattern or mask\$3 or inactiv\$5 or (activ\$5) or pattern or mask\$3 or inactiv\$5 or (activ\$5) or (a	ļ				
466	466 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) 27 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((((silicon or Si) near2) (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and (((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (adj activ\$5) or pattern\$3)) and (((427/525,553,555,558).CCLS.) ((427/226).CCLS.) ((147/28,395).CCLS.) ((147/252,533,555,588).CCLS.) ((147/252,533,555,588).CCLS.) ((147/248,1,255,18,255.23) or (de adj activ\$5) or deactiv\$5) or deactiv\$5) or of (adj activ\$5) or of of activ\$5	466					
layer or deposit\$3 or \$4CVD or vaporiz\$5)]) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) 27 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)]) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3])) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3])) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3])) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3])) and (((427/255, 253, 555, 558).CCLS.) ((427/248.1, 255.18, 255.23) or (438/503, 507)).CCLS.) ((427/248.1, 255.18, 255.23) or (438/503, 507)).CCLS.) ((427/248.1, 255.18, 255.23) or (438/48, 349).CCLS.)) ((127/248.1, 255.18, 255.23) or (438/503, 507)).CCLS.) ((427/248.1, 255.18, 255.23) or (527.271).CCLS.) ((427/258, 259, 261, 264, 265, 270, 271).CCLS.) ((427/258, 259, 261, 264, 265, 270, 271).CCLS.) ((427/258, 259, 261, 264, 265, 270, 271).CCLS.) ((427/248.1, 255.18, 255.23) or (527.271).CCLS.) ((427/248.1, 255.18, 255.23) or (628.271) (USPAT; US-PGPUB - 1 ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5)	layer or deposit\$3 or \$ACVD or vaporiz\$5)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or patternor or sin near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or patterns\$3)) and (((427/526,525,555,558).CCLS.) ((427/228,1,255,18,255,23) or (438/503,507)).CCLS.) ((427/248,1,255,18,255,23) or (438/503,507)).CCLS.) ((427/248,1,255,18,255,23) or (348/503,507)).CCLS.) ((123/348,349).CCLS.) ((117/88,95).CCLS.)) ((117/68,349).CCLS.) ((1	layer or deposit\$3 or \$4CVD or vaporiz\$51) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3])	_	466		IICDAT.	2002/11/04 11.42
vaporiz\$5)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))	vaporiz\$5)) and ((monolayer or (mono adj layer) or SAM or (self adj ascembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3))	vaporiz85))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) vith (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) vith (mask\$3 or sactVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) vith (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and ((427/525, 5253,555,558).CCLS.) ((427/226, 253,555,558).CCLS.) ((427/226, 259, 261, 264, 265, 270, 271).CCLS.) ((427/234, 259, 261, 264, 265, 270, 271).CCLS.) ((427/234, 259, 261, 264, 265, 270, 271).CCLS.) ((427/236, 259, 261, 264, 265, 270, 271).CCLS.) ((427/236) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or of captiv\$5 or (in adj activ\$5) or (de adj activ\$5) or of captiv\$5 or of capti			layer or deposit\$3 or \$4CVD or		2003/11/04 11:43
layer) or SAM or (self adj assembl\$3))	layer) or SAM or (self adj assembl\$3) with (mask3) or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3) ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) and (((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask3) or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/228.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)) ((layer) or SAM or (self adj assembls3)				OB-FGFOB	
with (mask\$3 or inactiv\$5 or (in adjactiv\$5) or pattern\$3)	## with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) 27 ((((stilicon or si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))) and (((427/525,253,555,558).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/228,25),253,555,558).CCLS.) ((427/226).CCLS.) ((427/288,259,261,264,265,270,271).CCLS.) ((427/288,259,261,264,265,270,271).CCLS.) ((427/288,259,261,264,265,270,271).CCLS.) ((17/68,313 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj activ\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5 - 1 ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or deactiv\$5) - 60 (tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) - 60 (tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (deactiv\$5) or (de	with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) 27 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or waporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and (((427,525,553,555,558).CCLS.) ((427,7286,1,255,18,255.23) or (438,503,507)).CCLS.) ((427,7286,1,255,18,255.23) or (438,503,507)).CCLS.) ((427,7286,349).CCLS.) ((117,788,95).CCLS.)) ((1427,7286,349).CCLS.) ((117,788,95).CCLS.)) ((1427,7286,349).CCLS.) ((117,788,95).CCLS.)) ((1427,7286,349).CCLS.) ((117,788,95).CCLS.)) ((1427,7286,349).CCLS.) ((117,788,95).CCLS.)) ((1427,7286,39).261,264,265,270,271).CCLS.) ((1427,7286,39).261,264,265,270,271).CCLS.) ((1427,7286,39).261,264,265,270,271).CCLS.) ((1427,7286,39).261,264,265,270,271).CCLS.) ((1427,7286,39).261,264,265,270,271).CCLS.) ((1427,7286,130).261,261,264,265,270,271).CCLS.) ((1427,7286,130).261,264,265,270,271).CCLS.) ((1427,7286,259,261,264,265,270,271).CCLS.)	1		laver) or SAM or (self adj assembl\$3))]
activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3]) 27 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$3])) and ((((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) 1 ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) 4 ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) 60 ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) 60 ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj activ\$5) or (de adj activ\$5) or deactiv\$5) or (de adj activ\$7) or (de	activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3)) 727 ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3))) and (((427/552,553,555,588).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.348).349).CCLS.) ((117/88,95).CCLS.) ((1427/248.348).349).CCLS.) ((117/88,95).CCLS.)) ((1427/248.348).349).CCLS.) ((117/88,95).CCLS.)) ((1427/248.313")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) (((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (deactiv\$5)	activ\$5) or deactiv\$5 or (de adj activ\$5) or patterns(3)) ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask3) or inactiv\$5 or (in adj activ\$5) or patterns(3))) and ((((427/525,553,555,558).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) (((17/288.259,261,264,265,270,271).CCLS.) ((427/258.259,261,264,265,270,271).CCLS.) ((427/258.259,261,264,265,270,271).CCLS.) ((427/258.259,261,264,265,270,271).CCLS.) ((17/288.259,261,264,265,270,271).CCLS.) ((17/288.259,261,264,265,270,271).CCLS.) ((17/288.259,261,264,265,270,271).CCLS.) ((17/288.259,261,264,265,270,271).CCLS.) ((17/288.259,261,264,265,270,271).CCLS.) ((17/27/261,265.253,555,588).CCLS.) ((17/27/261,CCLS.) ((17/27/261,CCLS.) ((17/27/261,CCLS.) ((17/27/261,CCLS.)) ((17/27/261,CCLS.) ((1		1	with (mask\$3 or inactiv\$5 or (in adi		i
or pattern\$3]) ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3]) and (((427/552,553,555,558).CCLS.) ((427/252,553,555,558).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((4217/258,259,261,264,265,270,271).CCLS.) (USPAT; US-PGPUB 3003/11/04 11:57 USPAT; US-PGPUB 4003/11/04 11:53 USPAT; US-PGPUB 41.53 41.54 42.55 43.56 44.56 45.56 45.56 46.56 47.56 48.56 48.57 49.56 49.	or pattern\$3]) 27 ((((s)(s)(c) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5])) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3])) and (((4277)525,253,555,558).CCLS.) ((427/2481,255.18,255.23) or (4387503,507)).CCLS.) ((427/2481,255.18,255.23) or (4387503,507)).CCLS.) ((427/248,1,255.18,255.23) or (4387503,507)).CCLS.) ((1427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((1427/258,259,261,264,265,270,271).CCLS.) ((4237348,349).CCLS.) ((1177/88,95).CCLS.)) - 1 ((tridecafluoro near3 triethoxysilane) or FAS13 or ("FAS1 3")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) - ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) - 60 ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (fe adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj assembl\$5	or pattern\$3)) (((((silicon or si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))) and (((427/252,553,555,558).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/248,1,255,18,255,23) or (438/503,507)).CCLS.) ((127/268,259,261,264,265,270,271).CCLS.) ((427/288,259,261,264,265,270,271).CCLS.) ((127/268,259,261,264,265,270,271).CCLS.) ((127/268,259,261,264,265,270,271).CCLS.) ((127/268,259,261,264,265,270,271).CCLS.) ((127/268,139)) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or deactiv\$5) or (de adj activ\$5) or (in adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (eactiv\$5) or (e	1				
27 (((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))) and ((((427/552,553,555,558).CCLS.) ((427/288.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((117/88,95).CCLS.)) 1 ((tridecafluoro near3 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) 1 ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (in adj activ\$5) or (de adj activ\$5) or or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (in adj activ\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or or (mono adj layer) or SAM or (self adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or or (de adj activ\$5) or or (deactiv\$5) or (de adj activ\$5) or (de adj activ	Continue	27	1		or pattern\$3))		
or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3))) and (((427/525,553,555,558).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)) 1 ((tridecafluoro near3 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj activ\$5) or deactiv\$5) or (de adj activ\$5) or or deactiv\$5) or (fast adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or (fast adj activ\$5) or deactiv\$5) or (fast adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (fast adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) 4 ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj activ\$5) or (in adj activ\$5) or (deactiv\$5) 4 ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj activ\$5) or deactiv\$5)	or layer or deposit§3 or \$4CVD or vaporiz§5)) and ((monolayer or (mono adj layer) or SAM or (self adj assembl§3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3])) and (((427/256.)CCLS.) ((427/226.)CCLS.) ((427/228.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)) ((tridecafluoro near3 triethoxysilane) or FASI3 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl§5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (adj activ\$5) or (self adj assembl§5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or (for adj activ\$5) or	or layer or deposit§3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or pattern\$3)) and (((427/526).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((1427/258,259,261,264,265,270,271).CCLS.) ((1427/258,259,261,264,265,270,271).CCLS.) ((1427/258,259,261,264,265,270,271).CCLS.) ((1428/348,349).CCLS.) ((117/88,95).CCLS.)) ((tridecafluoro near3 triethoxysilane) or FASI3 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or (de adj activ\$5) or (fax) ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or (de adj activ\$5) or deactiv\$5) or (de adj activ\$5) or deactiv\$5) or (de adj activ\$5) or (de adj	-	27		USPAT:	2003/11/04 11:53
<pre>vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3))) and (((427/552,553,555,558).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((tridecafluoro near3 triethoxysilane) or FASI3 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5') or (de adj activ\$5) or (eactiv\$5') ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5') or (de adj activ\$5) or deactiv\$5') ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5') or (de adj activ\$5) or deactiv\$5') ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj activ\$5') or deactiv\$5') ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj activ\$5') or deactiv\$5')</pre> <pre> 4 ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj</pre>	vaporiz\$\$))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (de adj activ\$5) or pattern\$31)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/2348,349).CCLS.)) ((427/258,259,261,264,265,270,271).CCLS.) ((427/2348,349).CCLS.) ((117/88,95).CCLS.)) ((1427/2348,349).CCLS.) ((117/88,95).CCLS.)) ((1646afluoro near\$ triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) ((tridecafluoro near\$ triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) ((tridecafluoro near\$ triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (fastiv\$5) or (de adj activ\$5) or deactiv\$5) (((tridecafluoro near\$ triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or (de adj activ\$5) or (de adj activ\$5) or (deactiv\$5) or (de adj activ\$5) or deactiv\$5) or (de adj activ\$5) or deactiv\$5) or (de adj activ\$5) or (deactiv\$5) or (de adj activ\$5) or (deactiv\$5) or (vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3)) and (((427/552,553,555,558).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or (428/348,349).CCLS.) ((17/88,95).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((17/788,95).CCLS.)) USPAT; (Utridecafluoro near3 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or (de adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or (de adj activ\$5) or deactiv\$5) or (de adj activ\$5) or (de adj acti			or layer or deposit\$3 or \$4CVD or		
layer) or SAM or (self adj assembl§3) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/226).CCLS.) ((427/228.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((1423/348,349).CCLS.) ((117/88,95).CCLS.)) (USPAT; US-PGPUB (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or (deactiv\$5) o	layer) or SAM or (self adj assembl§3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/248.1,255.18) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5] ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5] ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or deactiv\$5] ((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5) or deactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) r (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) or deactiv\$5] or deactiv\$5] or deactiv\$5] or deactiv\$5] or deactiv\$5]	layer) or SAM or (self adj assembl\$3) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3)) and (((427/526,553,555,558).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/228,1255,18,255.23) or (438/503,507).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((427/258,349).CCLS.) ((117/88,95).CCLS.)) 1 ((tridecafluoro near3 triethoxysilane) or FASI3 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) 1 ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) ((tridecafluoro near5 triethoxysilane) or FASI3 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) and (((427/526),503,505),508).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/228,259,261,264,265,270,271).CCLS.)			vaporiz\$5))) and ((monolayer or (mono adj		
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activ\$5) or deactiv\$5) (((tridecafluoro near5 triethoxysilane) or USPAT; USPAT; FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj	activ\$5) or deactiv\$5) (((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)	activ\$5) or deactiv\$5) (((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)			assembl\$5) or pattern or mask\$3 or		
4 (((tridecafluoro near5 triethoxysilane) or USPAT;	4 (((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)	4 (((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)			inactives or (in adj actives) or (de adj		
FAS13 or ("FAS 13")) and (monolayer or US-PGPUB (mono adj layer) or SAM or (self adj	FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)	FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)	_	ا ۸			
(mono adj layer) or SAM or (self adj	<pre>(mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)</pre>	(mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)		4	FAS13 or ("FAS 13")) and (manalage) or		2003/11/04 11:58
assembl\$5) or nattern or mask3 or	assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)	assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) (((427/258,259,261,264,265,270,271).CCLS.)	ļ		(mono adi laver) or SAM or (colf adi	US-PGPUB	
	inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)	inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)	1		assembl\$5) or pattern or mask\$3 or		
inactiv\$5 or (in adi activ\$5) or (do adi	activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)	activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)		j	inactiv\$5 or (in adj activ\$5) or (do adj		
activ\$5) or deactiv\$5)) and	(((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)	(((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)			activ\$5) or deactiv\$5)) and	Í	
(((427/552,553,555,558),CCLS.)	((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)	((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)	j		(((427/552,553,555,558).CCLS.)		
((427/226).CCLS.)	(((427/248.1,255.18,255.23) or (438/503,507)).CCLS.)	(((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)	į	1	((427/226).CCLS.)		
(((427/248.1,255.18,255.23) or	(438/503,507)).CCLS.)	(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)			(((427/248.1,255.18,255.23) or		
(438/503,507)).CCLS.)	[(427/258,259,261,264,265,270,271) core \	((427/258,259,261,264,265,270,271).CCLS.)			(438/503,507)).CCLS.)		
[(427/258,259,261,264,265,270,271) ccre v	[(([(423/348,349) CCLS) (/117/99 05) CCLC)]	ſ	1	((427/258, 259, 261, 264, 265, 270, 271), CCLS.)		
[(\\-\-\-\-\-\-\-\-\-\-\-\-\-\-\-\-\-\	((423/348,349).CCLS.) ((117/88.95).CCLS.))	[((111/00,31),.cch3.) ((11/00,33).cch3.))			((423/348,349).CCLS.) ((117/88,95).CCLS.))		

=	56	(((tridecafluoro near5 triethoxysilane) or	USPAT;	2003/11/04 12:01
		FAS13 or ("FAS 13")) and (monolayer or	US-PGPUB	
		(mono adj layer) or SAM or (self adj		
		assembl\$5) or pattern or mask\$3 or		
		inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) not		
		((((tridecafluoro near5 triethoxysilane)		
		or FAS13 or ("FAS 13")) and (monolayer or		
		(mono adj layer) or SAM or (self adj	i	Ì
		assembl\$5) or pattern or mask\$3 or		
		inactiv\$5 or (in adj activ\$5) or (de adj		
		activ\$5) or deactiv\$5)) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.)		
		((117/88,95).CCLS.)))		
-	0	((tridecafluoro near5 triethoxysilane) or	EPO; JPO;	2003/11/04 12:49
1		FAS13 or ("FAS 13")) and (monolayer or	DERWENT;	
		(mono adj layer) or SAM or (self adj	IBM_TDB	
		assembl\$5) or pattern or mask\$3 or	,	
		inactiv\$5 or (in adj activ\$5) or (de adj		
	1	activ\$5) or deactiv\$5)	HCDAT.	2003/11/04 12:51
-	4	Meeks.xp,xa. and (self adj assemb\$8)	USPAT; US-PGPUB	2003/11/04 12:31
_	46692	((Si or silicon) with (coat\$3 or film or	USPAT;	2003/11/04 12:59
	10052	layer or deposit\$3 or \$4CVD) with	US-PGPUB	2000,11,01 12.05
		(pattern\$3 or nonuniform\$3 or (non adj	00 10100	
		uniform\$3) or mask\$3))		
-	573	(((Si or silicon) with (coat\$3 or film or	USPAT;	2003/11/04 12:54
		layer or deposit\$3 or \$4CVD) with	US-PGPUB	
		(pattern\$3 or nonuniform\$3 or (non adj		
		uniform\$3) or mask\$3))) and		1
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		1
		((427/258,259,261,264,265,270,271).CCLS.)		
,	400	((423/348,349).CCLS.) ((117/88,95).CCLS.))	HCDAM.	2002/11/04 12:52
-	422	<pre>((((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with</pre>	USPAT; US-PGPUB	2003/11/04 13:52
		(pattern\$3 or nonuniform\$3 or (non adj	03-16105	•
		uniform\$3) or mask\$3))) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
	1	((427/258,259,261,264,265,270,271).CCLS.)		
	1	((423/348,349).CCLS.)		
		((117/88,95).CCLS.))) and ((monolayer or		
		(mono adj layer) or SAM or (self adj		
		assembl\$3)) or (mask\$3 or inactiv\$5 or (in		
	1	adj activ\$5) or deactiv\$5 or (de adj		
	21012	activ(5)))	HCDAM -	2002/11/04 10 55
-	31013	(((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with	USPAT; US-PGPUB	2003/11/04 12:57
		layer or deposits3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj	03-rGrub	
	1	uniform\$3) or mask\$3))) same ((monolayer		
		or (mono adj layer) or SAM or (self adj		
		assembl\$3)) or (mask\$3 or inactiv\$5 or (in		
		adj activ\$5) or deactiv\$5 or (de adj		
		activ\$5)))		
-	398	(((Si or silicon) with (coat\$3 or film or	USPAT;	2003/11/04 12:57
	1	layer or deposit\$3 or \$4CVD) with	US-PGPUB	
	}	(pattern\$3 or nonuniform\$3 or (non adj		
		uniform\$3) or mask\$3))) same ((monolayer		
		or (mono adj layer) or SAM or (self adj		
	-	assembl\$3)) or (inactiv\$5 or (in adj	}	
		activ\$5) or deactiv\$5 or (de adj activ\$5)))		
		CCTAA7111	l	1

[5	////Ci on ciliars) with /coatco as file	THATS	10000/11/01/10 55
		((((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj	USPAT; US-PGPUB	2003/11/04 12:57
		uniform\$3) or mask\$3))) same ((monolayer or (mono adj layer) or SAM or (self adj		
		assembl\$3)) or (inactiv\$5 or (in adj		
		activ\$5) or deactiv\$5 or (de adj activ\$5)))) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.) (((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)		
	*	((423/348,349).CCLS.) ((117/88,95).CCLS.))		
_	13228	((Si or silicon) adj (coat\$3 or film or layer or deposit\$3 or \$4CVD) with	USPAT; US-PGPUB	2003/11/04 13:02
		(pattern\$3 or nonuniform\$3 or (non adj	05 13105	
_	170	uniform\$3) or selecti\$6)) (((Si or silicon) adj (coat\$3 or film or	USPAT;	2003/11/04 13:01
		layer or deposit\$3 or \$4CVD) with	US-PGPUB	2000, 11, 01 20101
		(pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or selecti\$6))) and		
		(((427/552,553,555,558).CCLS.) ((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)		
	1600	((423/348,349).CCLS.) ((117/88,95).CCLS.))		
	1680	((Si or silicon) adj (coat\$3 or film or layer or deposit\$3 or \$4CVD) with	USPAT; US-PGPUB	2003/11/04 13:03
		(pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or selecti\$6) with (\$4CVD or		
		(vapor\$9)))	1	
_	37	(((Si or silicon) adj (coat\$3 or film or layer or deposit\$3 or \$4CVD) with	USPAT; US-PGPUB	2003/11/04 13:08
		(pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or selecti\$6) with (\$4CVD or		
		(vapor\$9)))) and		
		(((427/552,553,555,558).CCLS.) ((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)		
_	589	((423/348,349).CCLS.) ((117/88,95).CCLS.))	IICDAM.	2002/11/04 12 14
	303	\$4CVD) near2 (Si or silicon))	USPAT; US-PGPUB;	2003/11/04 13:14
			EPO; JPO; DERWENT;	
_	20	//solostive mean? /sost62 s	IBM_TDB	0000/41/5
	40	\$4CVD) near2 (Si or silicon))) and (SAM or	USPAT; US-PGPUB;	2003/11/04 13:32
		<pre>monolayer or (self adj assemb\$7) or (mono adj layer))</pre>	EPO; JPO; DERWENT;	
			IBM_TDB	
-	106	<pre>(selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon)) same</pre>	USPĀT; US-PGPUB;	2003/11/04 13:30
		pattern\$3	EPO; JPO;	
			DERWENT; IBM TDB	
-	103	((selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon)) same	USPAT;	2003/11/04 13:15
		<pre>pattern\$3) not (((selective near2 (coat\$3</pre>	US-PGPUB; EPO; JPO;	
	ļ	or deposit\$3 or \$4CVD) near2 (Si or silicon))) and (SAM or monolayer or (self	DERWENT; IBM TDB	
_	102	adj assemb\$7) or (mono adj layer)))	_	
-	103	<pre>(selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon))</pre>	EPO; JPO; DERWENT;	2003/11/04 13:32
	_		IBM TDB	

S4CVD) near2 (Si or silicon)) and (SAM or monolayer or (self adj assembs?) or (mono adj layer) or inactiv\$5 or mask\$3 or deactiv\$5 or (in adj activ\$5)) red (selective near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer))					
or monolayer or (self adj assemb\$7) or deactiv\$5 or (in adj activ\$5) or (de adj activ\$5)] 13 (selective near2 (coat\$3 or film or layer or deposit\$3 or \$40VD)) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer)) 109 (selective near2 (coat\$3 or film or layer or deposit\$3 or \$40VD)) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer)) - 109 (selective near2 (coat\$3 or film or layer or deposit\$3 or \$40VD)) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer)) - 17 ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$40VD)) and ((ring adj silane) or (cyclic adj silane) or silylevclopentasilane) or (sily near2 cyclopentasilane) or (syclo adj penta adj silane) or silylevclopentasilane) or silylevclopentasilane or si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (sily) near2 cyclopentasilane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or si6H12 or "Si.sub.5H.sub.10" or cyclos adj penta adj silane) or (cyclic adj silane) or cyclosilane or silylevclopentasilane) or (silyl near2 cyclopentasilane) (((silicon or Si) near2 (coat\$3 or film or "Si.sub.5H.sub.10" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.6 H.sub.12" or "Si.	_	29	((selective near2 (coat\$3 or deposit\$3 or	EPO; JPO;	2003/11/04 13:37
mono adj layer) or inactiv\$5 or mask\$3 or deactiv\$5)					
deactiv\$5 or (in adj activ\$5) or (de adj activ\$5)		1		IBM_TDB	
activ5)) (selective near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer)) 109 (selective near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer)) 70 (selective near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer) 71 ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si. sub.5 H. sub.10" or "Si. sub.5 H. sub.10" or "Si. sub.5 H. sub.10" or "Si. sub.6 H. sub.12" or "Si. sub.6 H. sub.12" or (cyclic adj silane) or cyclopentasilane) 141 ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclopentasilane) or (cyclic adj silane) or "Si. sub.5 H. sub.10" or "Si. sub.5 H. sub.10" or "cyclopentasilane or Si5H10 or "Si. sub.6 H. sub.12" or "sil. sub.6 H. sub.12" or "si					
13		ł	deactiv\$5 or (in adj activ\$5) or (de adj		
or deposit\$3 or \$4CVD) same (SAN or monolayer or (self adj assemb\$7) or (mono adj layer)) (selective near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) same (SAN or monolayer or (self adj assemb\$7) or (mono adj layer)) 7 "9707429" ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "\$i.sub.5 H.sub.10" or "\$i.sub.5 H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or (cyclo adj pentasilane) or cyclopentasilane) or cyclosilane or cyclopentasilane or Si6H12 or "\$i.sub.6H.sub.12"		1	activ\$5))		
monolayer or (self adj assemb\$7) or (mono adj layer)	_	13	(selective near2 (coat\$3 or film or layer	EPO; JPO;	2003/11/04 13:38
adj layer)) (selective near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer)) 7 "9707429" ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5HlO or "\$i.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si5HlO or "\$i.sub.5H.sub.10" or (cyclo adj penta) ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or silylcyclopentasilane or Si5HlO or "\$i.sub.6H.sub.12" or (silyl near2 cyclopentasilane)) ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclo adj penta) or cyclosilane or cyclopentasilane or Si5HlO or "\$i.sub.5H.sub.10" or (cyclo adj penta) or (silyl near2 cyclopentasilane)) or (cyclo adj penta) ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or silylcyclopentasilane or Si5HlO or "\$i.sub.6H.sub.12" or (silyl near2 cyclopentasilane)) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or cyclosilane or cyclopentasilane) or (cyclo adj penta) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or cyclosilane or cyclopentasilane) or (cyclo adj penta) or "\$i.sub.5H.sub.10" or "\$i.sub.5H.sub.10" or "\$i.sub.5H.sub.10" or "\$i.sub.5H.sub.10" or (cyclo adj penta) or "\$i.sub.5H.sub.10" or (cyclo adj penta) or "\$i.sub.5H.sub.10" or (cyclo adj penta) or "\$i.sub.5H.sub.10" or (cyclo adj penta) or cyclopentasilane) or (cyclo adj penta) or cyclopentasilane) or (cyclo adj penta) or cyclopentasilane) or (cyclo adj penta) or cyclopentasilane) or (cyclo adj penta) or cyclopentasilane) or (cyclo adj penta) or cyclopentasilane) or (cyclo adj penta) or cyclopentasilane) or (cyclopentasilane) or cyclopentasilane) or (cyclopentasilane) or (cyclopentasilane) or (cyclopentasilane) or (cyclopentasilane) or (cyclop					
109			monolayer or (self adj assemb\$7) or (mono	IBM_TDB	
or deposit\$3 or \$4¢VD) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer)) 7 "9707429" 2003/11/04 13:45 EPO; JPO; DERWENT; adj silane) or (cyclosidane or cyclopentasilane) or (cyclo adj silane) or (cyclosidane) or (cyclo adj penta adj silane) or (silyle pentasilane) or (cyclo adj penta adj silane) or (silyle near2 (coat\$3 or film or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silyleyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.10" or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj silane) or (
monolayer or (self adj assemb\$7) or (mono adj layer) - 37 "9707429" ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4¢VDI) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si. sub.5H sub.10" or "Si. sub.5H sub.10" or "Si. sub.5H sub.10" or "Si. sub.6H sub.12" or "Si. sub.6H sub.10" or "Si. sub.5H sub.10" or "Si. sub.6H sub.12" or "Si. sub.6H sub.	_	109	(selective near2 (coat\$3 or film or layer		2003/11/04 13:45
adj layer)) - 37 "9707429" ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or SiSH10 or "Si.sub.5H.sub.10" or "Si.sub.5H.sub.10" or "Si.sub.5H.sub.10" or "Si.sub.5H.sub.10" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.10" or (cyclo adj penta adj silane) or (cyclopentasilane) or (cyclogatis) and ((ring adj silane) or (cyclogatis) and ((ring adj silane) or (cyclogatis) and or (cyclogatis) or SiSH10 or "Si.sub.5H.sub.10" or "Si.sub.5H.sub.10" or "Si.sub.5H.sub.10" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.10" or (cyclogatis) and ((ring adj silane) or (cyclogatis) or \$4CVD)) and ((ring adj silane) or (cyclogatis) or \$4CVD)) and ((ring adj silane) or (cyclogatis) or \$4CVD) and (ring adj silane) or \$4CVD) and (ring adj silane) or \$4CVD] and (ring adj silane) or \$4CVD] and \$				US-PGPUB	1
- "9707429" ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclosadjane or syclopentasilane or Si5H10 or "\$i.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or (cyclo adj pentasilane) or (cyclo adj pentasilane) or cyclopentasilane or Si6H12 or "\$i.sub.6H.sub.12" or "\$i.sub.6H.sub.12" or "\$i.sub.6H.sub.12" or "\$i.sub.6H.sub.12" or "\$i.sub.6H.sub.12" or "\$i.sub.6H.sub.12" or "\$i.sub.6H.sub.12" or "\$i.sub.6H.sub.12" or "\$i.sub.6H.sub.12" or "\$i.sub.6H.sub.12" or "\$i.sub.5H.sub.10" or cyclosadj pentasilane) or (cyclo adj penta adj silane) or cyclosilane or cyclopentasilane or Si6H12 or "\$i.sub.5H.sub.10" or "\$i.sub.5H.sub.10" or "\$i.sub.6H.sub.12" or \$i.sub.6H.sub.12" or \$i.sub.6H.sub.12" or \$i.sub.6H.sub.12" or \$i.sub.6H.sub.12" or \$					
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37	-	7	"9707429 "		2003/11/04 13:45
layer or deposit\$3 or \$4(CVD)) and ((ring adj silane) or (cycloid adj silane) or cyclopentasilane or si5H10 or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.12" or (adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cycloid adj silane) or (cycloid adj silane) or (cycloid adj silane) or (cycloid adj silane) or (cycloid adj silane) or (cycloid adj silane) or (cycloid adj silane) or "Si.sub.5H.sub.10" or "Si.sub.5H.sub.10" or "Si.sub.5H.sub.10" or "Si.sub.6H.sub.12" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cycloid adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.5H.sub.10" or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or (cyclo adj silane) or (cyclo adj silane) or (c					
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or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) 141 ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) 14 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/226).CCLS.) ((427/228.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					}
H.sub.12" or (silyl near2 cyclopentasilane)) ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
cyclopentasilane) ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclor adj silane) or cyclosilane or cyclopentasilane or Si5HlO or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or "Si.sub.5H.sub.10" or "Si.sub.5H.sub.10" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.10" or cyclor adj silane) or cyclosilane or cyclopentasilane or Si5HlO or "Si.sub.5 H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6Hl2 or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.12" or "Si.sub.6H.sub.12" or (silyl near2 cyclopentasilane)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
141 ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) 14 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 ((427/252,553,555,558).CCLS.) ((427/261,CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) 14 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6 H.sub.12" or		1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1		TIODAM -	2002/11/04 14:01
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cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/228,259,261,264,265,270,271).CCLS.)				US-PGPUB	
or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) 14 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
"Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 ((427/552,553,555,558).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) 14 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/2552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/228,1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					,
H.sub.12" or (silyl near2 cyclopentasilane)) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5 H.sub.10" or (cyclo adj penta adj silane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and ((427/256,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
cyclopentasilane)) (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)			H sub 12" or (silvl poer?		
- 14 (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)	_	1 11		IIGDAT.	2003/11/04 13:52
adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)				1	2003/11/04 13:32
cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)				05 10105	
or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
"Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)	1				
silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)				1	
H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
(((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)				İ	
(((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)					
(438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)		1			
((427/258,259,261,264,265,270,271).CCLS.)					
		1			
((423/348,349).CCLS.) ((117/88,95).CCLS.))		[((423/348,349).CCLS.) ((117/88,95).CCLS.))		

-	127	(((silicon or Si) near2 (coat\$3 or film or	USPAT;	2003/11/04 13:52
		layer or deposit\$3 or \$4CVD)) and ((ring	US-PGPUB	
		adj silane) or (cyclic adj silane) or		
ĺ		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
	1	"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		1
ĺ		H.sub.12" or (silyl near2		
		cyclopentasilane))) not ((((silicon or Si)		
		near2 (coat\$3 or film or layer or		
		deposit\$3 or \$4CVD)) and ((ring adj		
		ailpro) or (eveling all (fring adj		İ
		silane) or (cyclic adj silane) or		
	1	cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		1
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12]
		or "Si.sub.6H.sub.12" or "Si.sub.6		
[H.sub.12" or (silyl near2	1	
	ĺ	cyclopentasilane))) and		
]		(((427/552,553,555,558).CCLS.)		
1		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
i		((427/258,259,261,264,265,270,271).CCLS.)		ĺ
		((423/348,349).CCLS.)		
		((117/88,95).CCLS.)))		
i –	2	((((silicon or Si) near2 (coat\$3 or film	USPAT;	2003/11/04 13:54
		or layer or deposit\$3 or \$4CVD)) and	US-PGPUB	2003/11/04 13:54
		((ring adj silane) or (cyclic adj silane)	OD-FGFOD	
		or cyclosilane or cyclopentasilane or		l
	ĺ	Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		j
i		pentasilane) or (cyclo adj penta adj		ĺ
	ĺ	silano) on silulanalananta-ilana ai cuto		
		silane) or silylcyclopentasilane or Si6H12		
ľ	ļ	or "Si.sub.6H.sub.12" or "Si.sub.6		
	i	H.sub.12" or (silyl near2		
}		cyclopentasilane))) not ((((silicon or Si)		
		near2 (coat\$3 or film or layer or		
		deposit\$3 or \$4CVD)) and ((ring adj		
[silane) or (cyclic adj silane) or	i	
		cyclosilane or cyclopentasilane or Si5H10		ļ
]		or "Si.sub.5 H.sub.10" or		
ľ		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		ļ
!		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2	İ	
		cyclopentasilane))) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
	Ī	(((427/248.1,255.18,255.23) or		ļ
		(438/503,507)).CCLS.)		
]	((427/258,259,261,264,265,270,271).CCLS.)		1
	1	((423/348, 349).CCLS.)		1
İ		((117/88,95).CCLS.)))) and ((monolayer or		İ
		(mono adj layer) or SAM or (self adj		
		assembl\$3)))		İ
		T 0 / / /		

- 12	25 ((((silicon or Si) near2 (coat\$3 or film	USPAT;	2003/11/04 13:54
	or layer or deposit\$3 or \$4CVD)) and	US-PGPUB	
	((ring adj silane) or (cyclic adj silane)		
	or cyclosilane or cyclopentasilane or		
	Si5H10 or "Si.sub.5 H.sub.10" or		
	"Si.sub.5H.sub.10" or (cyclo adj		
	pentasilane) or (cyclo adj penta adj		
	silane) or silylcyclopentasilane or Si6H12		
	or "Si.sub.6H.sub.12" or "Si.sub.6		
	H.sub.12" or (silyl near2		
	cyclopentasilane))) not ((((silicon or Si)	ł	
	near2 (coat\$3 or film or layer or	1	
	deposit\$3 or \$4CVD)) and ((ring adj		
	silane) or (cyclic adj silane) or		
	cyclosilane or cyclopentasilane or Si5H10	ļ	
	or "Si.sub.5 H.sub.10" or		
	"Si.sub.5H.sub.10" or (cyclo adj		
	pentasilane) or (cyclo adj penta adj		
	silane) or silylcyclopentasilane or Si6H12		
	or "Si.sub.6H.sub.12" or "Si.sub.6		
	H.sub.12" or (silyl near2		
	cyclopentasilane))) and		
	(((427/552,553,555,558).CCLS.)		
	((427/226).CCLS.)		
	(((427/248.1,255.18,255.23) or		
	(438/503,507)).CCLS.)		
	((427/258,259,261,264,265,270,271).CCLS.)		
•	((423/348,349).CCLS.)		
	((117/88,95).CCLS.)))) not ((((silicon or		
]	Si) near2 (coat\$3 or film or layer or		
1	deposit\$3 or \$4CVD)) and ((ring adj		
	silane) or (cyclic adj silane) or		
	cyclosilane or cyclopentasilane or Si5H10		
	or "Si.sub.5 H.sub.10" or		
1	"Si.sub.5H.sub.10" or (cyclo adj		
	pentasilane) or (cyclo adj penta adj		
	silane) or silylcyclopentasilane or Si6H12		
	or "Si.sub.6H.sub.12" or "Si.sub.6		
	H.sub.12" or (silyl near2		
	cyclopentasilane))) not ((((silicon or Si)		
	near2 (coat\$3 or film or layer or		1
	deposit\$3 or \$4CVD)) and ((ring adj		
	silane) or (cyclic adj silane) or		
	cyclosilane or cyclopentasilane or Si5H10		
	or "Si.sub.5 H.sub.10" or		
	"Si.sub.5H.sub.10" or (cyclo adj		
	pentasilane) or (cyclo adj penta adj		
	silane) or silylcyclopentasilane or Si6H12		
	or "Si.sub.6H.sub.12" or "Si.sub.6		
	H.sub.12" or (silyl near2 cyclopentasilane))) and	1	
		1	
	(((427/552,553,555,558).CCLS.) ((427/226).CCLS.)	1	
	1 ' ']	
	(((427/248.1,255.18,255.23) or		
	(438/503,507)).CCLS.)		
1	((427/258, 259, 261, 264, 265, 270, 271).CCLS.)		
	((423/348,349).CCLS.)		
	((117/88,95).CCLS.)))) and ((monolayer or	1	
	(mono adj layer) or SAM or (self adj	1	1
	assembl\$3))))		

_	11	((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj pentasilane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) and (ink adj jet\$4 or inkjet\$4 or (bubble adj jet\$4) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:03
-	1	bubblejet\$4) ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) same (ink adj jet\$4 or inkjet\$4 or (bubble adj jet\$4) or bubblejet\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:21
-	2	6527847.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/04 14:13
_	401	(\$4CVD or (vapor adj deposit\$3)) same ((gas or inert or nitrogen or N2 or "N.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/04 14:29
_	28	((\$4CVD or (vapor adj deposit\$3)) same ((gas or inert or nitrogen or N2 or "N.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:24
	67	((423/348,349).CCLS.) ((117/88,95).CCLS.)) (\$4CVD or (vapor adj deposit\$3)) same ((((inert or nonreactive or (non adj reactive) or noble) near2 gas\$4) or nitrogen or N2 or "N.sub.2" or hydrogen or H2 or "H.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:31
	66	((\$4CVD or (vapor adj deposit\$3)) same ((((inert or nonreactive or (non adj reactive) or noble) near2 gas\$4) or nitrogen or N2 or "N.sub.2" or hydrogen or H2 or "H.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))) not (((\$4CVD or (vapor adj deposit\$3)) same ((gas or inert or nitrogen or N2 or "N.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:31
_	5	6541354.pn. or 6503570.pn. or 6527847.pn. or "20030229190" or "20020034585"	USPAT; US-PGPUB	2004/04/22 13:49

_	3	6715871.pn. or 6646662.pn. or 6599582.pn.	USPAT; US-PGPUB	2004/04/22 13:50
-	39	(Furusawa.in. or Miyashita.in. or	USPAT;	2004/04/22 14:03
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj	EPO; JPO; DERWENT;	
	ľ	Epson).as.) and ((silicon or Si) near2	IBM TDB	
		(coat\$3 or film or layer or deposit\$3 or		
		\$4CVD)) and ((ring adj silane) or (cyclic		
		adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo	<u> </u>	
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))		
-	34	1 (USPAT;	2004/04/22 14:00
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj	EPO; JPO; DERWENT;	
		Epson).as.) and ((silicon or Si) near2	IBM TDB	
		(coat\$3 or film or layer or deposit\$3 or		
		\$4CVD)) and ((ring adj silane) or (cyclic		
		adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))) not (6541354.pn. or		
		6503570.pn. or 6527847.pn. or		
_	14	"20030229190" or "20020034585")		000440440
-	14	(((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or	USPAT; US-PGPUB;	2004/04/22 14:04
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or	IBM_TDB	
		\$4CVD)) and ((ring adj silane) or (cyclic		
		adj (silane or silicon)) or cyclosilane or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
]	H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
	<u> </u>	H.sub.12" or (silyl near2		
		cyclopentasilane))) not (6541354.pn. or 6503570.pn. or 6527847.pn. or		
		"20030229190" or "20020034585")) and		
	ļ	(active with inactive with \$4CVD or (vapor		
_	1	near2 deposit\$3))		0001/01/00
		(((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or	USPAT; US-PGPUB;	2004/04/22 14:02
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or	IBM_TDB	
		\$4CVD)) and ((ring adj silane) or (cyclic		
		adj (silane or silicon)) or cyclosilane or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj		
]	silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		İ
		H.sub.12" or (silyl near2		
		cyclopentasilane))) not (6541354.pn. or 6503570.pn. or 6527847.pn. or	İ	
		"20030229190" or "20020034585")) and		
		(active with inactive with (\$4CVD or		
		(vapor near2 deposit\$3)))		

-	1	(((Furusawa.in. or Miyashita.in. or	USPAT;	2004/04/22 14:02
İ	ļ	Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
	1	Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((silicon or Si) near2	IBM_TDB	
		(coat\$3 or film or layer or deposit\$3 or]
		\$4CVD)) and ((ring adj silane) or (cyclic		
		adj (silane or silicon)) or cyclosilane or	<u> </u>	
		cyclopentasilane or Si5H10 or "Si.sub.5		1
İ		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		<u> </u>
1		adj pentasilane) or (cyclo adj penta adj	ŀ	
		silane) or silylcyclopentasilane or Si6H12		1
1		or "Si.sub.6H.sub.12" or "Si.sub.6		į
		H.sub.12" or (silyl near2		
		cyclopentasilane))) not (6541354.pn. or]
		6503570.pn. or 6527847.pn. or		
		"20030229190" or "20020034585")) and		1
	İ	(active with inactive)		ĺ
_	26	· ·	USPAT;	2004/04/22 14:04
]		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	2001,01,22 11.01
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
İ		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	ŧ
		Epson).as.) and (((silicon or Si) near2	IBM TDB	1
		(coat\$3 or film or layer or deposit\$3 or	1211_122	
		\$4CVD)) same (\$4CVD or (vapor near2		
		deposit(\$3))) and ((ring adj silane) or		
		(cyclic adj (silane or silicon)) or		
		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj	ĺ	
		pentasilane) or (cyclo adj penta adj		1
		silane) or silylcyclopentasilane or Si6H12		i l
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
	,	cyclopentasilane))		
-	4	(Furusawa.in. or Miyashita.in. or	USPAT;	2004/04/22 14:07
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	l
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
İ		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and (active with inactive with	IBM_TDB	
	_	(\$4CVD or (vapor near2 deposit\$3)))		
-	3	1 · ·	USPAT;	2004/04/22 14:05
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	ļ
		Epson).as.) and (active with inactive with	IBM_TDB	
		(\$4CVD or (vapor near2 deposit\$3)))) not		l i
		((((Furusawa.in. or Miyashita.in. or		
]		Yudasaka.in. or Shimoda.in. or		
		Yokoyama.in. or Matsuki.in. or		
		Takeuchi.in. or JSR.as. or (Seiko adj		
		Epson).as.) and ((silicon or Si) near2		
]		(coat\$3 or film or layer or deposit\$3 or		
]		\$4CVD)) and ((ring adj silane) or (cyclic		
1		adj (silane or silicon)) or cyclosilane or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
	'	adj pentasilane) or (cyclo adj penta adj	•	
]		silane) or silylcyclopentasilane or Si6H12		
1		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))) not (6541354.pn. or		
		6503570.pn. or 6527847.pn. or		
		"20030229190" or "20020034585")) and		
		(active with inactive))		
				L

_	2	(Furusawa.in: or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and (active with inactive with (SAM or monolayer or (mono adj layer) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:09
-	2	monomolecular or (mono adj molecular) or (self adj assemb\$5))) (Furusawa.in. or Miyashita.in. or	USPAT;	2004/04/22 14:11
		Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((SAM or monolayer or (mono adj layer) or monomolecular or (mono adj molecular) or (self adj assemb\$5)) with (region or active or inactive or pattern\$3 or (arrang\$4 near2 liquid) or area) with (\$4CVD or (vapor near2 deposit\$3)))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	
_	11	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((SAM or monolayer or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/22 14:11
		<pre>(mono adj layer) or monomolecular or (mono adj molecular) or (self adj assemb\$5)) with (\$4CVD or (vapor near2 deposit\$3)))</pre>		
_	9	Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((SAM or monolayer or (mono adj layer) or monomolecular or (mono	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:11
		adj molecular) or (self adj assemb\$5)) with (\$4CVD or (vapor near2 deposit\$3))) not ((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj		
		Epson).as.) and ((SAM or monolayer or (mono adj layer) or monomolecular or (mono adj molecular) or (self adj assemb\$5)) with (region or active or inactive or pattern\$3 or (arrang\$4 near2 liquid) or area) with (\$4CVD or (vapor near2		
-	1492	deposit\$3)))) (427/552,553,555,558).CCLS.	USPAT; US-PGPUB	2004/04/22 15:34
-	2363	((427/248.1,255.18,255.23) or (438/503,507)).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	2908	(427/258,259,261,264,265,270,271).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	427	(423/348,349).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
_	542 7427	(117/88,95).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
	1421	((427/552,553,555,558).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)	USPAT; US-PGPUB	2004/04/22 15:36

-	14	(((427/552,553,555,558).CCLS.)	USPAT;	2004/04/22 15:43
		(((427/248.1,255.18,255.23) or	US-PGPUB	
		(438/503,507)).CCLS.)		
1		((427/258, 259, 261, 264, 265, 270, 271).CCLS.)		•
		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
		and ((silicon or Si) near2 (coat\$3 or film		
		or layer or deposit\$3)) and ((ring adj		
		silane) or (cyclic adj silane) or		
		cyclosilane or cyclopentasilane or Si5H10		
		or "Si.sub.5 H.sub.10" or		
1		"Si.sub.5H.sub.10" or (cyclo adj	1	
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
	3	cyclopentasilane))		
-	3	(((427/552,553,555,558).CCLS.) or	USPAT;	2004/04/22 15:39
		((427/258,259,261,264,265,270,271).CCLS.))	US-PGPUB	
		and ((ring adj silane) or (cyclic adj		
		silane) or cyclosilane or cyclopentasilane		
		or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
1		cyclopentasilane))		
_	34	((((427/248.1,255.18,255.23) or	USPAT;	2004/04/22 15:42
	0.1	(438/503,507)).CCLS.) and	US-PGPUB	2004/04/22 15:42
		((427/258,259,261,264,265,270,271).CCLS.))	US-FGFUB	
		((12172307233720172047203721072117.0CLS.))		
_	4862	(((427/552,553,555,558).CCLS.)	USPAT;	2004/04/22 15:42
		((427/226).CCLS.)	US-PGPUB	2001/04/22 15.42
		(((427/248.1,255.18,255.23) or	** 10102	
		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
		and (((silicon or Si) near2 (coat\$3 or		
		film or layer or deposit\$3 or \$4CVD or		
		<pre>vaporiz\$5)) with (select\$7 or pattern\$3 or</pre>		Í
1 '		nonuniform or (non adj uniform))) and		
]	((monolayer or (mono adj layer) or		
		fluoroalkyl or fluorine or SAM or (self		
1		adj assembl\$3) or fluoro\$12) with (mask\$3		
1]	or inactiv\$5 or (in adj activ\$5) or		
		<pre>deactiv\$5 or (de adj activ\$5))))</pre>		
-	0	((((427/248.1,255.18,255.23) or	USPAT;	2004/04/22 15:43
		(438/503,507)).CCLS.) and	US-PGPUB	
		((427/258,259,261,264,265,270,271).CCLS.))		
		and ((423/348,349).CCLS.)		
1-	0	((427/258, 259, 261, 264, 265, 270, 271).CCLS.)	USPAT;	2004/04/22 15:44
		and ((ring adj silane) or (cyclic adj	US-PGPUB	
		(silane or silicon)) or cyclosilane or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
	ļ [H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		ĺ
]		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
.		or "Si.sub.6H.sub.12" or "Si.sub.6		
1 '	1 }	H.sub.12" or (silyl near2		
	1	cyclopentasilane))		

-	14	(((427/552,553,555,558).CCLS.) or	USPAT;	2004/04/22 15:59
	1	(((427/248.1,255.18,255.23) or	US-PGPUB	
	1	(438/503,507)).CCLS.) or		
		((117/88,95).CCLS.)) and ((ring adj		
		silane) or (cyclic adj (silane or		
		silicon)) or cyclosilane or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))	TIGDAM -	2004/04/20 15:46
-	34	(((427/248.1,255.18,255.23) or	USPAT;	2004/04/22 15:46
· ·		(438/503,507)).CCLS.) and	US-PGPUB	
		((427/258,259,261,264,265,270,271).CCLS.)		1
-	123	1 , , , , , , , , , , , , , , , , , , ,	USPAT;	2004/04/22 15:48
		(((427/248.1,255.18,255.23) or	US-PGPUB	
		(438/503,507)).CCLS.)		1
		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.))		
		and ((\$4CVD or (vapor near2 deposit\$3) or		<u> </u>
		vaporiz\$4) same ((pattern\$3 or active or		j
		inactive or region) near6 (liquid or		!
		source or reagent or solution)))		<u> </u>
_	7	((ring adj silane) or (cyclic adj	USPAT;	2004/04/22 16:05
		(silane or silicon)) or cyclosilane or	US-PGPUB	2004/04/22 10:05
		cyclopentasilane or Si5H10 or "Si.sub.5	00 10100	
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
	j	adj pentasilane) or (cyclo adj penta adj		
]			
		silane) or silylcyclopentasilane or Si6H12		
	İ	or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane)) same (pattern\$3 or		1
		selectiv\$5)		·
-	30	((ring adj silane) or (cyclic adj	USPAT;	2004/04/22 16:04
		(silane or silicon)) or cyclosilane or	US-PGPUB	
]	cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		l
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane)) same (vapor\$9 or \$4CVD)		
_	9	((ring adj silane) or (cyclic adj	USPAT;	2004/04/23 08:31
		(silane or silicon)) or cyclosilane or	US-PGPUB	2004/04/25 00.31
		cyclopentasilane or Si5H10 or "Si.sub.5	JO EGEOD	
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
1		cyclopentasilane)) same (SAM or monolayer		
		or monomolecular or (mono adj (layer or		
		molecular)) or (self adj assemb\$5) or		
		mask\$3 or photomask\$3)		
-	103	(((ring adj silane) or (cyclic adj	USPAT;	2004/04/23 08:32
		(silane or silicon)) or cyclosilane or	US-PGPUB;	
		cyclopentasilane or Si5H10 or "Si.sub.5	EPO; JPO;	
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo	DERWENT;	
		adj pentasilane) or (cyclo adj penta adj	IBM TDB	
1		silane) or silylcyclopentasilane or Si6H12]
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
]		cyclopentasilane)) same (pattern\$3 or		
		select\$5))		
	L		L	

		T 1		
-	26	(((ring adj silane) or (cyclic adj	USPAT;	2004/04/23 08:36
		(silane or silicon)) or cyclosilane or	US-PGPUB;	
		cyclopentasilane or Si5H10 or "Si.sub.5	EPO; JPO;	
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo	DERWENT;	
ļ		adj pentasilane) or (cyclo adj penta adj	IBM_TDB	
İ		silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane)) same ((pattern\$3 or select\$5) with (coat\$3 or film or layer or		
		deposit\$4 or \$4CVD or apply\$4)))		
_	37	(((vapor near2 deposit\$3) or \$4CVD)	IICDAT.	2004/04/23 08:45
]	near3 (selecti\$6 or pattern\$5 or	USPAT; US-PGPUB;	2004/04/23 06:45
		nonuniform\$4 or (non adj uniform\$5))) and	EPO; JPO;	•
		((evaporat\$5 or vaporiz\$5) near3 (liquid	DERWENT;	
		or reagent or solution or source or	IBM TDB	
		crucible or material) near3 (pattern or	1201_122	
		select\$7))		
_	38549	(((vapor near2 deposit\$3) or \$4CVD or	USPAT;	2004/04/23 08:48
		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB;	2004/04/25 00:40
	*	layer) near3 (selecti\$6 or pattern\$5 or	EPO; JPO;	
		nonuniform\$4 or (non adj uniform\$5))) and	DERWENT;	
		((liquid or reagent or solution or source	IBM TDB	
		or crucible or material) with (pattern or		
		select\$7 or region) with (mask\$3 or		
1		monolayer or SAM or (self adj assemb\$5) or	1	
		(mono adj layer) or monomolecular or (mono		}
		adj molecular)))		
-	690	(((vapor near2 deposit\$3) or \$4CVD or	USPAT;	2004/04/23 08:50
		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB;	
		layer) near3 (selecti\$6 or pattern\$5 or	EPO; JPO;	
		nonuniform\$4 or (non adj uniform\$5))) and	DERWENT;	
		((liquid or reagent or solution or source	IBM TDB	
		or crucible or material) with (pattern or	_	
		select\$7 or region) with (monolayer or SAM		
		or (self adj assemb\$5) or (mono adj layer)		
		or monomolecular or (mono adj molecular)))		
-	463	((((vapor near2 deposit\$3) or \$4CVD or	USPAT;	2004/04/23 08:53
		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB;	İ
ļ		layer) near3 (selecti\$6 or pattern\$5 or	EPO; JPO;	
		nonuniform\$4 or (non adj uniform\$5))) and	DERWENT;	
}		((liquid or reagent or solution or source	IBM_TDB	
		or crucible or material) with (pattern or		
		select\$7 or region) with (monolayer or SAM		
		or (self adj assemb\$5) or (mono adj layer)		
		or monomolecular or (mono adj		
		molecular)))) and (evaporat\$5 or vaporiz\$5		
		or \$4CVD or (vapor adj deposit\$3))	, , , , , , , , , , , , , , , , , , ,	0004/04/05 55
-	74	(((vapor near2 deposit\$3) or \$4CVD or	USPAT;	2004/04/23 08:50
		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB;	
		layer) near3 (selecti\$6 or pattern\$5 or	EPO; JPO;	
		nonuniform\$4 or (non adj uniform\$5))) and ((liquid or reagent or solution or source	DERWENT;	
			IBM_TDB	
		or crucible or material) with (pattern or	1	
]	<pre>select\$7 or region) with (monolayer or SAM or (self adj assemb\$5) or (mono adj layer)</pre>		
]	or monomolecular or (mono adj molecular))		
		with (mask\$3 or activ\$5 or inactiv\$5))		
_	17	((((vapor near2 deposit\$3) or \$4CVD or	USPAT;	2004/04/23 08:58
	- '	coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB;	2004/04/23 00:38
		layer) near3 (selecti\$6 or pattern\$5 or	EPO; JPO;	
		nonuniform\$4 or (non adj uniform\$5))) and	DERWENT;	
		((liquid or reagent or solution or source	IBM TDB	
		or crucible or material) with (pattern or		
		select\$7 or region) with (monolayer or SAM		
		or (self adj assemb\$5) or (mono adj layer)		
		or monomolecular or (mono adj molecular))		
		with (mask\$3 or activ\$5 or inactiv\$5)))		
		and ((evaporat\$5 or vaporiz\$5 or \$4CVD or		
		(vapor adj deposit\$3)) with (selectiv\$5 or		
		pattern\$4 or region or portion))		
			L	L

	1 000	1 (0 A GY ID	1	10001/01/00 00
-	883	(\$4CVD or vaporiz\$5 or evaporat\$5 or (vapor adj deposit\$3)) near3 (crucible or	USPAT; US-PGPUB;	2004/04/23 09:00
		source or surface) near3 (pattern\$3 or	EPO; JPO;	
		(active near3 inactive))	DERWENT;	
		(decive fields indecive))	IBM TDB	
1 -	123	(\$4CVD or vaporiz\$5 or evaporat\$5 or	USPAT;	2004/04/23 09:09
		(vapor adj deposit\$3)) near3 (crucible or	US-PGPUB;	2001,01,23
		source) near3 (pattern\$3 or (active near3	EPO; JPO;	[]
	-	inactive))	DERWENT;	
			IBM TDB	
-	6	((\$4CVD or coat\$3 or film or layer or	USPAT;	2004/04/23 09:12
		deposit\$3) near3 (selectiv\$4 or	US-PGPUB;]
		pattern\$3)) and ((liquid or solution or	EPO; JPO;	
		reagent) near6 (surface or substrate)	DERWENT;	
	615	near6 (active near4 inactive))	IBM_TDB	
-	615	((\$4CVD or coat\$3 or film or layer or	USPAT;	2004/04/23 09:13
		deposit\$3) near3 (selectiv\$4 or	US-PGPUB;	
		pattern\$3)) and (((liquid or solution or	EPO; JPO;]
		reagent) near6 (surface or substrate) near6 (pattern\$3 or select\$7)) same (\$4CVD	DERWENT;	
		or vapor\$9 or evaporat\$5))	IBM_TDB	
_	9407		USPAT;	2004/04/23 09:14
		((427/332,333,333,330).cclls.)	US-PGPUB	2004/04/23 09:14
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.)		
-	39	1 , , , ,	USPAT;	2004/04/23 09:19
		deposit\$3) near3 (selectiv\$4 or	US-PGPUB	
		pattern\$3)) and (((liquid or solution or		
		reagent) near6 (surface or substrate)		
		near6 (pattern\$3 or select\$7)) same (\$4CVD		
		or vapor\$9 or evaporat\$5))) and	İ	
		(((427/552,553,555,558).CCLS.) ((427/226).CCLS.)		
		((427/228).ccls.) (((427/248.1,255.18,255.23) or		
İ		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.)		
))		
-	22		USPAT;	2004/04/23 09:20
		coat\$3 or apply\$3 or deposit\$4 or film or	US-PGPUB	====
		layer) near3 (selecti\$6 or pattern\$5 or		
		nonuniform\$4 or (non adj uniform\$5))) and		
		((liquid or reagent or solution or source		
1]	or crucible or material) with (pattern or		
		select\$7 or region) with (monolayer or SAM		
		or (self adj assemb\$5) or (mono adj layer)		
		or monomolecular or (mono adj molecular)))) and		
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		(((427/248.1,255.18,255.23) or		
		(438/503,507)).CCLS.)		
		((427/258,259,261,264,265,270,271).CCLS.)		
		((423/348,349).CCLS.) ((117/88,95).CCLS.)		
))		
-	56		USPAT;	2004/04/23 09:23
		(crucible or source or liquid or solution)	US-PGPUB;	
		near2 (selectiv\$5 or pattern\$3))	EPO; JPO;	
			DERWENT;	
_	01	///wanan adi dani+62) A.a	IBM_TDB	
-	81	(((vapor adj deposit\$3) or \$4CVD) near3	USPAT;	2004/04/23 09:27
		(crucible or source or liquid or solution) near3 (mask\$3 or SAM or monolayer or	US-PGPUB;	
	į	monomolecular or (mono adj (layer or	EPO; JPO;	
		molecular)) or (self adj assembl\$4)))	DERWENT; IBM TDB	
L	L		TDM IND	

_	11	(((vapor adj deposit\$3) or \$4CVD) near3 (selectiv\$5 or pattern\$3)) and ((mask\$3 or inactiv\$5) near4 (SAM or monolayer or monomolecular or (mono adj (layer or	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/23 09:30
-	18	molecular)) or (self adj assembl\$4))) (((vapor adj deposit\$3) or \$4CVD or coat\$3 or film or deposit\$3 or layer or apply\$3) near3 (selectiv\$5 or pattern\$3)) and ((inactiv\$5) with (activ\$5) with (\$4CVD or (vapor near2 deposit\$4)))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/23 09:33
-	40	(liquid or solution) near2 (vaporiz\$5 or evaporat\$4) near2 pattern\$3	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/23 09:34
_	2	((liquid or solution) near2 (vaporiz\$5 or evaporat\$4) near2 pattern\$3) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:33
_	90	(liquid or solution) near3 (vaporiz\$5 or evaporat\$4) near3 pattern\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/23 09:34
_	2	((liquid or solution) near3 (vaporiz\$5 or evaporat\$4) near3 pattern\$3) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:34
_	88	((liquid or solution) near3 (vaporiz\$5 or evaporat\$4) near3 pattern\$3) not (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 10:26